

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	190740	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 10:43
L2	1118	L1 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:33
L3	171	L2 and lithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:37
L4	61	L3 and (position or align or alignment) same (shift or move or movement or change or alter or alteration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:23
L5	54	L4 and thin same film	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:43
L6	2	("20050181546").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/09/26 11:53
L7	7	L3 and (position or align or alignment) same (shift or move or movement or change or alter or alteration) same (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 11:59
L8	3	(US-20040197939-\$ or US-20040058540-\$ or US-20030064422-\$).did.	US-PGPUB	OR	ON	2006/09/26 11:59

## EAST Search History

L9	3	L8 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:52
L10	3	L8 and (position or align or alignment) same (shift or move or movement or change or alter or alteration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:23
L11	3	L10 and (pvd or (vapor same deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:39
L12	3	L8 and (pvd or (vapor same deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:28
L13	3	L12 and deposition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:39
L14	3	L11 and thin same film	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 12:48
L15	3	L8 and thin same film	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:35
L16	2	L8 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorithm\$4) and thin same film and deposition and (pvd or cvd or pecvd)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:39

## EAST Search History

L17	3	L8 and (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:43
L18	2	L8 and (thin same film) same (resist or photoresist)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:35
L19	2	L18 and lithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:37
L20	2	L19 and (pvd or (vapor same deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:52
L21	2	L20 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorithm\$4) and thin same film and deposition and (pvd or cvd or pecvd)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:40
L22	3	L8 and wafer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:48
L23	3	L8 and (computer or control\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:17
L24	1	L8 and (computer or control\$4) same (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:50

## EAST Search History

L25	3	L23 and (pvd or (vapor same deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 13:54
L26	2	L23 and (pvd or (vapor same deposition)) and (program or memory)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 14:14
L34	2	L8 and center	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:21
L35	2	L8 and rotation\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:23
L36	2	L8 and (rotation\$3 or rotate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:26
L37	2	L8 and (rotation\$3 or rotat\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:29
L38	3	L8 and (remov\$4 or etch\$4) and layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:33
L39	3	L8 and (remov\$4 or etch\$4) and layer and mark\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:50

## EAST Search History

L40	3	L8 and (material or layer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:51
L41	3	L8 and (insulat\$4 or conduct\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:52
L42	1	L8 and (insulat\$4 or conduct\$4) and (metal or metallic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:57
L43	2	L8 and (ccd or camera)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/26 16:58
S69	21788	438/6,10,104,107,108,109,110,111, 112,113,114,118,121,122,123,128, 129,135,142,145,149,151,157,176, 478,184,193,195,196,197,198,200, 201,202,203,206,207,209,210,211, 218,237,165,294,308,337,353,378, 401,410.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/13 08:38
S70	182273	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/13 08:38
S71	23457	438/6,10,104,107,108,109,110,111, 112,113,114,118,121,122,123,128, 129,135,142,145,149,151,157,176, 478,184,193,195,196,197,198,200, 201,202,203,206,207,209,210,211, 218,237,165,294,308,337,353,378, 401,410.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 21:02
S72	190610	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 21:13

## EAST Search History

S73	1118	S72 and (pvd or (vapor same deposition)) and (position or align or alignment) same (wafer or layer) and (resist or photoresist) and (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:32
S74	171	S73 and lithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:33
S75	61	S74 and (position or align or alignment) same (shift or move or movement or change or alter or alteration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:36
S76	54	S75 and thin same film	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:35
S77	7	S74 and (position or align or alignment) same (shift or move or movement or change or alter or alteration) same (formula or equation or algorithm\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/25 23:36
S78	3	(US-20040197939-\$ or US-20040058540-\$ or US-20030064422-\$).did.	US-PGPUB	OR	ON	2006/09/26 00:26